

Appl. No. 10/645,879  
Reply to Office action of 04/28/2005

### **REMARKS**

Reconsideration of the above-referenced application in view of the above amendment, and of the following remarks, is respectfully requested.

Claims 1, 2, 6-10, 12, 13, and 27 are pending in this case. Claims 1, 9, and 27 are amended herein and claims 3-5, 11, and 14-26 are cancelled herein.

The Examiner asserted that the title should be amended to correct the spelling of atmospheric. Applicant respectfully submits that the title was amended in the amendment dated March 29, 2005 to correct the spelling.

The Examiner rejected claims 1-13, 27 under 35 U.S.C. 102(b) as being anticipated by Wydeven (U.S. Patent 6,555,835 B1) and Meder (U.S. Patent 6,254,689 B1).

Applicant respectfully submits that claim 1 is unanticipated by Wydeven as there is no disclosure or suggestion in Wydeven of a housing adapted to enclose a semiconductor wafer, an ultraviolet radiation source disposed within the housing; and a treatment medium disposed within the housing, wherein the treatment medium comprises ambient air. Wydeven teaches a UV-ozone oxidation system which includes UV lamps positioned above a heated sample. Wydeven teaches flowing ozone or an ozone/oxygen mix into the chamber. Contrary to the Examiners assertion, Wydeven fails to disclose or suggest a treatment medium comprising ambient air. Wydeven only teaches the use of ozone and oxygen as a treatment medium. Accordingly, Applicant respectfully submits that amended claim 1 and the claims dependent thereon are unanticipated by Wydeven.

Applicant respectfully submits that amended claim 1 is unanticipated by Meder as there is no disclosure or suggestion in Meder of a housing adapted to enclose a

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semiconductor wafer, an ultraviolet radiation source disposed within the housing; and a treatment medium disposed within the housing, wherein the treatment medium comprises ambient air. Meder teaches two embodiments for cleaning a chamber that has been used for removing photoresist. Only the embodiment of FIG. 2 addresses a UV source within the housing. Oxygen is mentioned as an incoming gas. Air is mentioned in the embodiment of FIG. 1, but not with the embodiment of FIG. 2. Accordingly, Applicant respectfully submits that claim 1 and the claims dependent thereon are unanticipated by Meder.

Applicant respectfully submits that amended claim 9 is unanticipated by Wydeven and Meder as there is no disclosure or suggestion in either reference of a housing adapted to enclose a semiconductor wafer, an ultraviolet radiation source disposed within the housing, a treatment medium disposed within the housing; and a medium conditioning system disposed within the housing, wherein the medium conditioning system is adapted to induce a partial vacuum within the housing. Neither Wydeven nor Meder addresses a partial vacuum within the housing. Accordingly, Applicant respectfully submits that claim 9 and the claims dependent thereon are unanticipated by Wydeven and Meder.

Applicant respectfully submits that amended claim 27 is unanticipated by Wydeven and Meder as there is no disclosure or suggestion in either reference of a system for remediating organic contaminants from a copper seed layer deposited on an upper surface of a semiconductor wafer. Meder teaches a method for removing photoresist contamination from a photoresist removal tool. Meder does not disclose or suggest remediating organic contaminants from a copper seed layer. Wydeven teaches an oxidation system for forming an oxide layer. Wydeven, likewise, does not disclose or suggest a system for remediating organic contaminants from a copper seed layer.

Wydeven and Meder further do not disclose or suggest a conditioning system disposed within the housing and adapted to filter contaminants from the ozone, wherein the conditioning system is further adapted to induce a partial vacuum within the

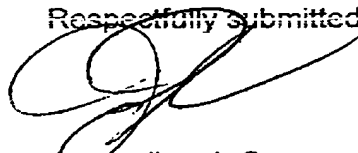
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housing. Neither reference discusses a partial vacuum within the housing. Accordingly, Applicant respectfully submits that claim 27 is unanticipated by both Wydeven and Meder.

The other references cited by the Examiner have been reviewed, but are not felt to come within the scope of the claims as amended.

In light of the above, Applicant respectfully requests withdrawal of the Examiner's rejections and allowance of claims 1, 2, 6-10, 12, 13, and 27. If the Examiner has any questions or other correspondence regarding this application, Applicant requests that the Examiner contact Applicant's attorney at the below listed telephone number and address.

Respectfully submitted,



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